

WHAT IS CLAIMED IS:

1. An apparatus comprising:
a wafer adapted to fit on a wafer stage of a lithography tool;
a radiation detector attached to a surface of the wafer, the radiation detector to produce a signal corresponding to an amount of radiation detected from the lithography tool; and
a processor coupled to the radiation detector, the processor to process the signal from the radiation detector.
2. The apparatus of Claim 1, further comprising a transmitter coupled to the processor, the transmitter to wirelessly transmit a signal from the processor.
3. The apparatus of Claim 1, wherein the detector is adapted to detect a dose of radiation from the lithography tool.
4. The apparatus of Claim 1, wherein the detector is adapted to detect an intensity of radiation from the lithography tool.

5. The apparatus of Claim 1, wherein the detector comprises an array of detectors.

6. The apparatus of Claim 1, further comprising alignment marks adapted to align the wafer on the wafer stage of the lithography tool.

7. The apparatus of Claim 1, further comprising an amplifier coupled to the radiation detector and the processor, the amplifier to amplify the signal from the radiation detector and transfer the amplified signal to the processor.

8. The apparatus of Claim 1, further comprising a power source coupled to the processor.

9. A system comprising:

a processor; and

a radiation detector adapted to communicate with the processor, the radiation detector to fit on a wafer stage of a lithography tool, the radiation detector to detect an amount of radiation from the lithography tool and transmit data corresponding to the amount of radiation to the processor, the processor to compare the data corresponding to the amount of radiation to a setting of the lithography tool.

10. The system of Claim 9, wherein the processor is adapted to use the data corresponding to the amount of radiation to calibrate the lithography tool.

11. The system of Claim 9, wherein the radiation detector is adapted to wirelessly transmit data to the processor.

12. An apparatus comprising:

a wafer sized to fit on a wafer stage of a lithography tool;

a radiation detector attached to a surface of the wafer, the radiation detector to produce a signal corresponding to an amount of radiation from the lithography tool;

a processor coupled to the radiation detector, the processor to process the signal from the radiation detector; and

a memory coupled to the processor, the memory to store data from the processor, the data corresponding to an amount of radiation from the lithography tool.

13. The apparatus of Claim 12, further comprising an output connector adapted to output data from the memory.

14. The apparatus of Claim 12, further comprising a transmitter coupled to the memory, the transmitter to wirelessly transmit data from the memory.

15. An apparatus comprising:

a wafer sized to fit on a wafer stage of a lithography tool;

a radiation detector fabricated on a surface of the wafer, the radiation detector to produce a signal corresponding to an amount of radiation from the lithography tool;

a processor attached to the surface of the wafer, the processor coupled to the radiation detector, the processor to process the signal from the radiation detector and output the data to the lithography tool.

16. The apparatus of Claim 15, further comprising a memory to store data from the processor.

17. A method comprising:

loading a wafer-shaped detector on a wafer stage of a first lithography tool;

detecting an amount of radiation from the first lithography tool; and

transmitting a first signal indicative of the amount of radiation detected by the detector.

18. The method of Claim 17, wherein said transmitting comprises wirelessly transmitting the first signal indicative of the amount of radiation detected by the detector.

19. The method of Claim 17, further comprising aligning the wafer-shaped detector on the wafer stage.

20. The method of Claim 17, further comprising converting the first signal corresponding to the amount of radiation detected by the detector to a second signal adapted to be wirelessly transmitted.

21. The method of Claim 17, wherein said detecting the amount of radiation comprises measuring a dose of radiation.

22. The method of Claim 17, wherein said detecting the amount of radiation comprises measuring an intensity of radiation.

23. The method of Claim 17, further comprising amplifying the first signal from the detector.

24. The method of Claim 17, further comprising removing the wafer-shaped detector from the wafer stage.

25. The method of Claim 17, further comprising comparing the amount of radiation detected by the detector to a pre-determined reference value.

26. The method of Claim 25, further comprising adjusting a setting of the lithography tool if the amount of radiation detected by the detector does not substantially match the pre-determined reference value.

27. The method of Claim 26, further comprising repeating said detecting an amount of radiation from the first lithography tool on the detector, and transmitting a second signal indicative of the amount of radiation from the first lithography tool detected by the detector.

28. The method of Claim 17, further comprising:
loading the wafer-shaped detector on a wafer stage in a second lithography tool;

detecting an amount of radiation from the second lithography tool; and

transmitting a second signal indicative of the amount of radiation detected by the detector.

29. The method of Claim 28, further comprising comparing the amount of radiation detected by the detector in the first lithography tool to the amount of radiation detected by the detector in the second lithography tool.